

WHAT IS CLAIMED IS:

1. An apparatus for processing a specimen which is laminated on a substrate, comprising:

5 an etching process unit, which is supplied with a gas to produce a plasma, for etching a specimen laminated on a substrate having two or more layers, at least one of which comprises NiFe or NiFeCo alloy, at a temperature of said specimen below 200°C;

10 a rinsing unit for rinsing an exposed surface of said lamination layer comprising said alloy, which is exposed by said etching, using a liquid; and

15 a dryer unit for drying said exposed surface of said lamination layer comprising said alloy after the rinsing thereof, wherein said lamination layer comprising said alloy which is dried is further subjected to gas plasma etching.

2. ~~An apparatus for processing a specimen according to claim 1, further comprising:~~

~~an atmospheric loader;~~

20 ~~a vacuum transport chamber having a vacuum transport robot therein; and~~

unload and load lock chambers connecting between said atmospheric loader and said vacuum transport chamber for delivering the specimen, wherein

said vacuum transport chamber is connected to said etching process chamber of said apparatus, and

said atmospheric loader is connected to at least a rinsing cup and hot plate provided in said rinsing/dryer units.

3. An apparatus for processing a specimen according to claim 1, wherein plural etching process chambers are provided.